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The effect of surface passivation on the microwave characteristics of undoped AlGa<sub>N</sub>/Ga<sub>N</sub> HEMTs

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IEEE Electron Device Letters, 2000, 21, 268-270.

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#	Paper	IF	Citations
605	Microwave Al <sub>x</sub> Ga <sub>1-x</sub> N/GaN Power HEMTs. <b>2000</b> , 639, 821		
604	AlGa <sub>N</sub> /Ga <sub>N</sub> MODFETs on semi-insulating SiC with 3 W/mm at 20 GHz. <b>2000</b> , 36, 1234		12
603	Fabrication and performance of GaN electronic devices. <b>2000</b> , 30, 55-212		373
602	Validation of an analytical large signal model for AlGa <sub>N</sub> /Ga <sub>N</sub> HEMT's on SiC substrates.		5
601	Effect of passivation on AlGa <sub>N</sub> /Ga <sub>N</sub> HEMT device performance.		6
600	Characteristics of AlGa <sub>N</sub> /Ga <sub>N</sub> HEMT devices with Si <sub>3</sub> N <sub>4</sub> passivation.		
599	Performance and limitations of AlGa <sub>N</sub> /Ga <sub>N</sub> HFETs grown on sapphire and SiC substrates.		3
598	Microwave performance of AlGa <sub>N</sub> /Ga <sub>N</sub> metal insulator semiconductor field effect transistors.		1
597	The gate-length dependent performance of AlGa <sub>N</sub> /Ga <sub>N</sub> HFETs with silicon nitride passivation.		2
596	Passivation of AlGa <sub>N</sub> /Ga <sub>N</sub> heterostructures with silicon nitride for insulated gate transistors.		19
595	Cascode connected AlGa <sub>N</sub> /Ga <sub>N</sub> HEMTs on SiC substrates. <b>2000</b> , 10, 316-318		20
594	Mechanism of radio-frequency current collapse in Ga <sub>N</sub> /AlGa <sub>N</sub> field-effect transistors. <b>2001</b> , 78, 2169-2171		85
593	Induced strain mechanism of current collapse in AlGa <sub>N</sub> /Ga <sub>N</sub> heterostructure field-effect transistors. <b>2001</b> , 79, 2651-2653		90
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591	Gallium nitride based transistors. <b>2001</b> , 13, 7139-7157		82
590	Growth of crack-free hexagonal GaN films on Si(100). <b>2001</b> , 79, 1459-1461		30
589	AlGa <sub>N</sub> /Al <sub>N</sub> /Ga <sub>N</sub> high-power microwave HEMT. <i>IEEE Electron Device Letters</i> , <b>2001</b> , 22, 457-459	4.4	340

588	Influence of barrier thickness on the high-power performance of AlGa <sub>N</sub> /Ga <sub>N</sub> HEMTs. <i>IEEE Electron Device Letters</i> , <b>2001</b> , 22, 504-506	4.4	116
587	Low-k BCB passivated Al/sub 0.5/Ga/sub 0.5/As/In/sub 0.15/Ga/sub 0.85/As enhancement-mode pHEMTs.		
586	High-power AlGa <sub>N</sub> /Ga <sub>N</sub> FET-based VCO sources.		1
585	Modeling and limitations of AlGa <sub>N</sub> /Ga <sub>N</sub> HFETs.		3
584	Novel Ga <sub>N</sub> -based MOS HFETs with thermally oxidized gate insulator.		1
583	Si <sub>3</sub> N <sub>4</sub> /AlGa <sub>N</sub> /Ga <sub>N</sub> metal insulator semiconductor heterostructure field effect transistors. <b>2001</b> , 79, 2832-2834		223
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516	Thermal simulations of high power, bulk GaN rectifiers. <b>2003</b> , 47, 1037-1043	10
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158	. <b>2016</b> , 15, 947-955	35
157	Scattering analysis of 2DEG mobility in undoped and doped AlGa <sub>N</sub> /Al <sub>N</sub> /Ga <sub>N</sub> heterostructures with an in situ Si <sub>3</sub> N <sub>4</sub> passivation layer. <b>2016</b> , 118, 12-17	4

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154	Optimization of the source field-plate design for low dynamic RDS-ON dispersion of AlGa <sub>N</sub> /Ga <sub>N</sub> MIS-HEMTs. <b>2017</b> , 214, 1600601		2
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148	Effect of Surface Passivation on the Electrical Characteristics of Nanoscale AlGa <sub>N</sub> /Ga <sub>N</sub> HEMT. <b>2017</b> , 225, 012095		3
147	Breakdown Enhancement and Current Collapse Suppression by High-Resistivity Ga <sub>N</sub> Cap Layer in Normally-Off AlGa <sub>N</sub> /Ga <sub>N</sub> HEMTs. <i>IEEE Electron Device Letters</i> , <b>2017</b> , 38, 1567-1570	4.4	48
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142	Substrates and Materials. <b>2017</b> , 27-52		
141	Interface Si donor control to improve dynamic performance of AlGa <sub>N</sub> /Ga <sub>N</sub> MIS-HEMTs. <b>2017</b> , 7, 125023		1
140	DC and RF Performance of AlGa <sub>N</sub> /Ga <sub>N</sub> /SiC MOSHEMTs With Deep Sub-Micron T-Gates and Atomic Layer Epitaxy MgCaO as Gate Dielectric. <i>IEEE Electron Device Letters</i> , <b>2017</b> , 38, 1409-1412	4.4	13
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138	Development of HEMT device with surface passivation for a low leakage current and steep subthreshold slope. <b>2017,</b>	1
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